

# PERFORMANCE EVALUATION OF LEAKAGE CONTROLLER IN 10T SRAM CELL STRUCTURES BY USING ADIABATIC TECHNIQUE

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## **ABSTRACT:**

Memory is a data storage system that is commonly used to preserve data as a machine memory on an integrated circuit built on a semiconductor. It is manufactured in different styles and technologies. Many other current semi-conductor cognitive devices are installed that require random access, and access to the data can be rendered in any random order in an efficient way. Random Static Access Memories (SRAM) is a form of semi-conductor storage memory that uses a flip flop to store each bit. There are 6 transistors in the shape of cross-connected inverters. This cell consists of two stable states that show 0 and 1. During reading and typing activities, two additional input transistors control entry to the storage cell.

Within the CMOS circuits it is important to dissipate power from the short circuit such that there are paths directly to the ground from  $V_{DD}$ . The adiabatic technique can overcome this disadvantage. Tanner EDA is the method for extracting the tests. The power produced for the traditional Memory cell is 2.2mW and the adiabatic technique suggested is 0.3mW

*Index Terms- Complementary Metal Oxide- Semiconductor (CMOS), Static Random Access Memory(SRAM).*

## **INTRODUCTION**

The power utilization, field, yield and yield of developing convenient electronic hardware are constrained by installed static irregular access recollections (SRAMs). These gadgets need low force utilization with the goal that they keep going long, as they are for the most part worked by

the batteries. The plan of SRAM foundations is ordinary, as a quadratic partner will limit the vitality utilization by diminishing the gracefully voltage[1]. The unpredictability of S RAM is, be that as it may, fundamentally improved by arrangement and strategy boundaries comparable to the right framework qualities proportion since the voltage is underneath the transistor limit voltage[2]. Serious issues of solidness under the SRAM sub-limit include the fluctuation of the gadgets brought about by the procedure which diminishes the ION/IOFF apportion and the irregular variety of edge voltage [3]. On account of the read-current-perturbance-initiated static commotion edge (SNM), the ordinary 6 T bit cell battles to direct viable low speculation tasks. A few morethan-6 T bit cells have been introduced, for example, 8 T bit cells[4] [5], to address perusing unwavering quality issues. They acquainted two transistors with isolated the registering hub from the bitline, which builds comprehensibility. For ultralow voltage SRAMs, the delicate blunder issue is more basic than sublime edge SRAMs, on the grounds that the basic burden at capacity hubs is impressively less. As observed in [6], with each 10% voltage decrease in flexibly, the delicate mistake rate increases

by 18 percent. The bit interlink strategy is frequently picked with the expectation of expanding SRAM sub-edges' delicate blunder resistance. It will spatially disconnect portions of one term in succession and it needs only the slightest bit mistake fix coding. Regardless, there was a compose half pick interruption in the read cradled 8 T bit cell built utilizing the bit-interruption strategy. The difficulty was tackled in a 12 percent overhead cluster plan and circuits, comparative with 8T SRAM [7]. Through decoupling huge bitline capacitances from half chose cells, the exhibit configuration handled the inquiry half chose. In [8], a 10 T bit high-meaningfulness differential cell has been distinguished. Meanwhile, vertical and level word lines might be developed utilizing somewhat interlinking strategy. To hold powerful composing activity, it required improved word line procedure. There was as of late a completely differential 8 T SRAM in [9] with a powerful section gracefully framework. Through using distinctive cell flexibly voltages in basic modes, the read/compose/reserve process has effectively been detached to permit a touch of interlocking. Inside this rundown, we recommend a cell of 9 T bit with an improved composing potential by including

a cross-associated transistor. Two extra composed word lines (WWL/WWLb) are utilized to help the interleaving arrangement plot bit of 9 T bit cells. Fundamental discoveries have been introduced in [ 10] first. Propelled solidness survey and exploratory tests from the created test chip iso-territory SRAM are depicted in these articles.

### **LITERATURE SURVEY**

Wang and A. Wang and A. On the Fast Fourier transformer, Chandrakasan [5] has developed new logic sub-thresholds and the methodologies for memory design. The energy-aware architecture is used by the FFT processor to calculate the approximate minimum energy point by providing variable FFT-length (128-1024 dots) and variable bit accuracy (8 b and 16 b), and is usable. FFT is made using a regular logic cycle of 0.18 $\mu$ m CMOS and can operate up to 180mV.

B.H.-B.H. A. Chandrakasan and Calhoun [6]. Have proposed a document which overcomes the limits of conventional six-transistor low voltage activity. We propose an alternate bit cell that operates at slightly lower voltages. The calculations show that an SRAM 256-kb 65-nm chip with the bit cell is below 400mV. The

memory at this low voltage provides considerable reductions in power and resources at the expense of capacity, which is ideal for energy constrained applications.

In order to analyze N-curve readability metrics and compare them with the most commonly used Static Noise Margin, L.Chang, D.M.Fried, J.Hergenrother, J. W.Sleight, R. H. Dennard, R.K.Montoye, L.Sekaric, S.J.McNab, and A.W.Topol [6] have suggested. In accordance with the standard writ-trip concept, the New write capacity metrics from the N-curve are used. Ultimately, the measures are used to measure the impact of intra-die volatility on cell stability using a statistically aware circuit optimization method and contrasting the outcomes with the worst case and corner configuration.

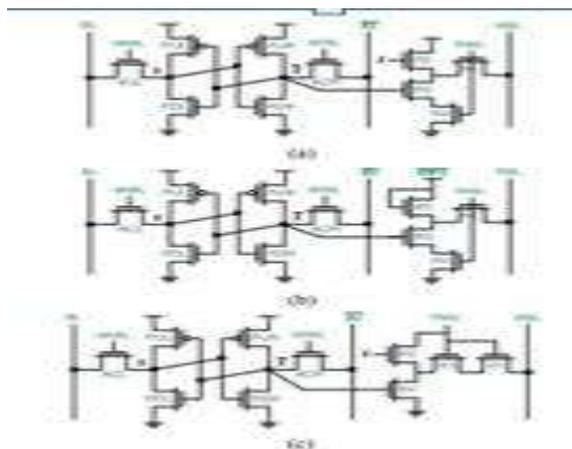
The applications highly energetic, such as wireless sensor Nods and biomedical implants have been suggested by M.E.Sinangil, N.Verma and A.P.Chandrakasan [10]. Ideally at low voltage and low frequency they are near the minimum SRAM power point for sub- $V_t$  and supra- $V_t$  operations. The geometry is 250mV, which is the nominal  $V_{DD}$  of the device, in a profound sub- $V_t$  area of 1,2V.

**EXISTING SYSTEM:**

**Existing SRAM BIT CELLS:**

**Topology of Proposed Bit Cells:**

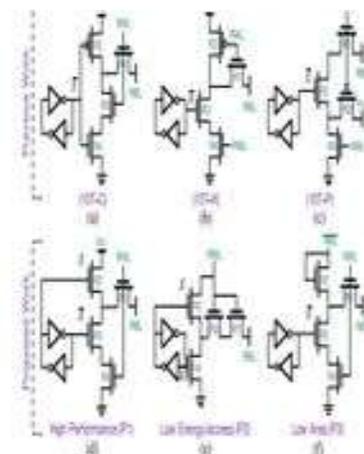
The 10 T SRAM cell structure is appeared in Fig. 2. The two transistors comprise of cross-coupled (PUL-PDL and PUR-PDR) inverters, and two ACL and ACR transistors, separately. Four NMOS (R1 , R2 , R3 and R4) are utilized in every cell's understood channel. The Fig reading port. 2(a) has enhanced bit line read leakage based on data and is configured to achieve high efficiency. The Fig read ports. 2(b) and (c) have full read-line leakage, independent of data and are targeted at very high power and low density. Within the next segment, the function of each port was clarified. From this point on, 10T-P1, 10T-P2, 10T- P3 are the suggested cells.



**Fig.1.Schematic of the proposed (a) 10T-P1 (b)10T-P3(c)10T –P2 cells.**

**Bit Cell Working Mechanism:**

The  $I_{ON} / I_{OFF}$  is severely weakened while working in the close and under-threshold area and more and more cells in a single column are being placed. The cumulative moving door leakage becomes equal with reading current as the percentage of layers grows and therefore it is impossible for the tactile amplifier to accurately determine reading bit-line voltage speeds. Moreover, a data and in cell often causes that same reading bit-line error and hence the reading bit-line existing that flows off-state fluctuates considerably. At ultralow voltages, this is compounded by the worst-counter data trend that may contribute to 'zero' RBL voltage rates being greater than one.



**Fig. 2 Schematic of read port of (a) Calhoun and Chandrakasan [1](b) Kim et al.[3](c)Pasandi and Fakharie[2] (d) Proposed 10T-P1(e)10T-P2 (f)10T-P3 cell.**

The read port shown in Fig is used to improve the  $I_{ON} / I_{OFF}$  ratio. 2(a) has been proposed. When the cell stores one, the R2 pMOS charges the interim node, which decreases the reading bit-line leakage by R1 nMOS substantially. However, the leakage flow from the intermediate node still contributes to the RBL. The joint leakage on the same column of all cells can increase RBL 's low logical level to several hundred millivolts and thereby reduce the voltage fluctuation and sensing margin. Fig:2 demonstrates the hypothetical scenario for the successful read-bit-line voltage swing for this situation. On the other hand, the RBL leakage is reduced by the stacking effect of nMOS when cell stories are "zero." In this manner, such a geography for the most part relies upon the segment 'sinformation design for the compelling RBL swing. The information reliance was additionally expelled in another work[3] by giving an information self-sufficient course between the cell read port and the RBL. The voltage of the RBL even at lower voltages was important. In Fig.3, you can see the read port and the effectiveness of the control RBL swing. In a recent paper[2], a changed reading port [in Fig.] has also been proposed. 2.(c)],  $I_{ON} / I_{OFF}$  ratio boost. The information subordinate spillage way issue

is, be that as it may, likewise influenced. The leakage from the intermediate node to the RBL will significantly alter, based on the data stored in the cell, contributing to differing RBL logic voltage rates. Given this issue, as shown in Figure, it can sustain an RBL swing. (c). 3(c). The cells in Fig from here on. The 10T-C, 10T-K and 10T-P cells are respectively listed in 2(a), (b ) and ( c). Unlike the cells mentioned, these cells do have the same write port topology and vary just as far as reading is concerned.

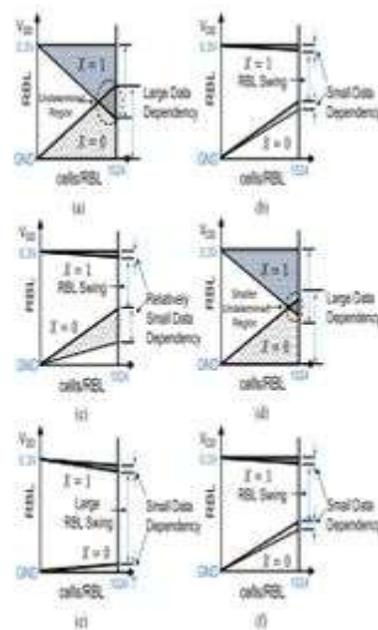


Fig:3 shows the schemes of the proposed read ports. [3](d)-(f). The 10T-P2 and 10T-P3 cells proposed are configured to be small power and low range while retaining an  $I_{ON} / I_{OFF}$  data-independent ratio, respectively. Figure describes the concept behind their work. 3(c) and (d), respectively. As in the fig:3. For both read 'none' and read 'one' scenario,  $I_{leak}$ 's magnitude is equivalent. For both instances, this helps to preserve the necessary magnitude gap between the cell current obtained. A major RBL shift, as seen in Figure, can therefore be shown. The three paragraphs of (e) and (f). Due to the heavy reliance on the data pattern of the leakage, conventional 8 T cell detection is not feasible.

Although 10T-P1 decreases its data dependency on the 10T-C as can be seen in Fig.3(d), the application for registration at ultra-low voltages remaining largely unable to be conducted. In the following segment, however, we demonstrate that operating at ultralow voltages improves the energy per entry and is optimum for lowest energy consumption by working close to the threshold level. The 10T-P1 cell is accordingly being worked near the sub-edge district, giving least vitality utilization and most extreme yield. The read bitline development is likewise not an issue for the 10T-P1 cell at close edge and high limit voltages.

### **PROPOSED ADIABATIC SRAM STRUCTURE AND ITS WORKING.**

Low power circuits that use "Reversible logic" to conserve energy are adiabatic circuits. Unlike conventional CMOS circuits, the energy-saving circuits during switching limit dissipation by two main rules: 1. Adiabatic circuits When voltage between source and drain exists, never turn on a transistor. 2. When the current flows through it, never turn off a transistor. There are several typical solutions to dynamic power reduction such as voltage reduction, physical capability decrease and the switching operation reduction. These techniques are not sufficiently suitable to meet current power needs. Yet most work has been centered on developing adiabatic logic, a successful low-power architecture. Adiabatic reasoning operates with the swapping principle that decreases control by supplying back the accumulated energy. The term adiabatic rationale is in this manner utilized in low-vitality, reversible VLSI circuits. This spotlights on the significant structure changes in the force clock that assumes the key job in the working standard. The two key design standards

on the adiabatic circuit framework might be cultivated in any purpose of the control clock.

- Never turn on a transistor if there is a voltage across it ( $V_{DS} > 0$ )
- Never turn off a transistor if there is a current through it ( $I_{DS} \neq 0$ )
- Never pass current through a diode.

In the event that these conditions concerning the contributions, in all the four periods of intensity clock, recuperation stage will reestablish the vitality to the force clock, coming about significant vitality sparing. However a few complexities in adiabatic rationale configuration propagate. Two such complexities, for example, are circuit usage for time-fluctuating force sources should be done and computational execution by low overhead circuit structures should be followed. There are two major difficulties of vitality recouping circuits; first, gradualness as far as the present principles, second it requires ~50% of more territory than regular CMOS, and basic circuit plans get convoluted. The essential ideas of adiabatic rationale will be presented. "Adiabatic" is a term of Greek beginning that has burned through the majority of its history related with old style thermodynamics. It alludes to a framework

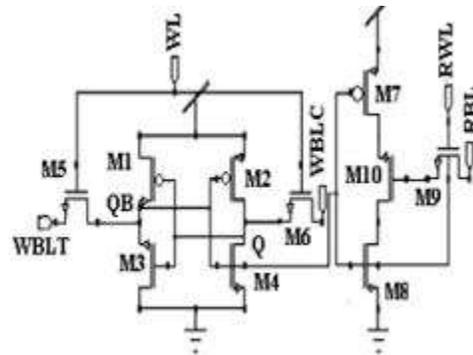
where a change happens without vitality (as a rule as warmth) being either lost to or picked up from the framework. Historical underpinnings of the expression "adiabatic rationale". Considering the Second Law of Thermodynamics, it is past the domain of creative mind to thoroughly change over imperativeness into accommodating work. In any case, the expression "Adiabatic Logic" is utilized to portray rationale families that could hypothetically work without misfortunes. The expression "Semi Adiabatic Logic" is utilized to depict rationale that works with a lower power than static CMOS rationale, yet which despite everything has some hypothetical non-adiabatic misfortunes. In the two cases, the classification is utilized to demonstrate that these frameworks are fit for working with considerably less force dispersal than conventional static CMOS circuits.

There are a few significant rules that are shared by these low-power adiabatic frameworks. These remember possibly turning switches for when there is no likely distinction across them, possibly turning turns off when no flow is coursing through them, and utilizing a force gracefully that is fit for recuperating or reusing vitality as electric charge. To accomplish this, as a rule, the force supplies of adiabatic rationale

circuits have utilized steady current charging (or an estimation thereto), as opposed to increasingly conventional non-adiabatic frameworks that have commonly utilized consistent voltage charging from a fixed-voltage power gracefully. The force supplies of adiabatic rationale circuits have additionally utilized circuit components equipped for putting away vitality. This is regularly done utilizing inductors, which store the vitality by changing over it to attractive motion. There are various equivalent words that have been utilized by different creators to allude to adiabatic rationale type frameworks, these include: "Charge recuperation rationale", "Charge reusing rationale", "Clockpowered rationale", "Vitality recuperation rationale" and "Vitality reusing rationale". In view of the reversibility necessities for a framework to be completely adiabatic, the vast majority of these equivalents really allude to, and can be utilized reciprocally, to depict semi adiabatic frameworks. These terms are brief and plain as day, so the main term that warrants further clarification is "Clock-Powered Logic". This has been utilized in light of the fact that numerous adiabatic circuits utilize a joined force flexibly and clock, or a "power-clock". This variable, for the most part multi-stage, power-gracefully

which controls the activity of the rationale by providing vitality to it, and along these lines recouping vitality from it. Since high-Q inductors are not accessible in CMOS, inductors must be off-chip, so adiabatic exchanging with inductors are restricted to plans which utilize just a couple of inductors. Semi adiabatic stepwise charging maintains a strategic distance from inductors totally by putting away recouped vitality in capacitors. Stepwise charging (SWC) can use on-chip capacitors.

In this adiabatic circuit one can guarantee that both the bit lines are charged to similar voltages before perusing. The different advances engaged with composing, perusing and hold activities in the new circuit. In both the ordinary SRAM and the proposed adiabatic SRAM, the information which must be composed is first gotten with its supplement utilizing two altering cushions as appeared in Fig.4.

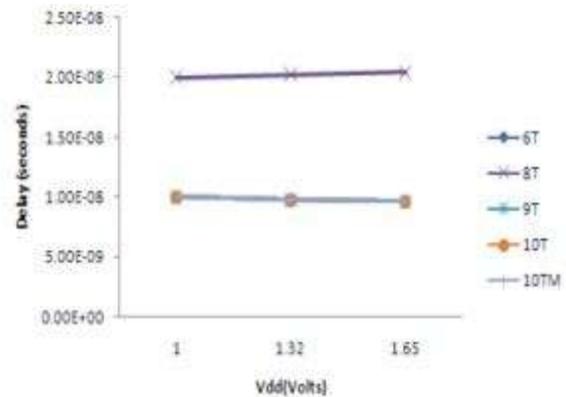


**Fig:4 Schematic of 10T SRAM Cell.**

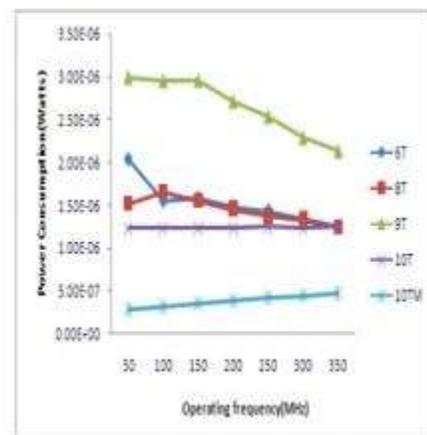
The schematics of the 10 T substratum bit cell are seen in Fig.4.[6] Transistors are the same as the 6 T bit cell except the M1 and M2 connection connects to a  $V_{DD}$  virtual power supply. The written cell access is given by M5 and M6 written access transistors, Writing bit line transistors, WBLT and WBLC. Memory controllers M8 through M10 install a buffer for read-only reading control, which is pre-recharged to RBL before a read-only entry. The word line for reading is often distinct from the word line for publishing. Some of the main benefits to distinguish the read and write terms and bit lines is that a processor will have multiple read / write ports for this bit cell.

**SIMULATION PERFORMANCE AND ANALYSIS**

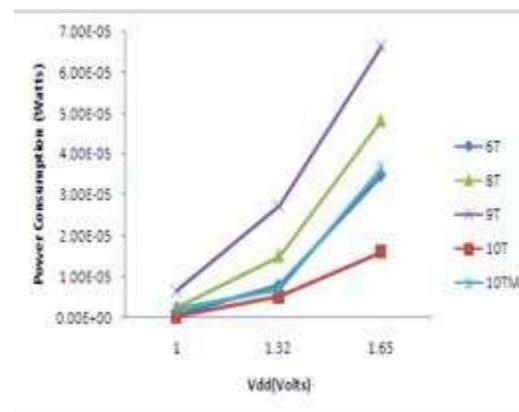
The whole circuit was simulated on a Tanner EDA device with a selection of supply voltage using 18 nm technology. Both circuits were replicated using the same input data to allow the unbiased testing area. The above listed comparative circuit study of the technology 90 nm, 45 nm and 32 nm. Simulation findings reveal that the strongest 10 T Adjusted SRAM cell performs in power usage, follow an open and temperature at 90 nm and 45 nm tech and 10 T SRAM cell at 18 nm technology.



**Fig:5 Delay vs.  $V_{DD}$  for Different SRAM Cell.**



**Fig:6 Power Consumption vs. Operating Frequency for Different SRAM Cells.**



**Fig:7 Power Consumption vs.  $V_{DD}$  for Different SRAM Cells.**

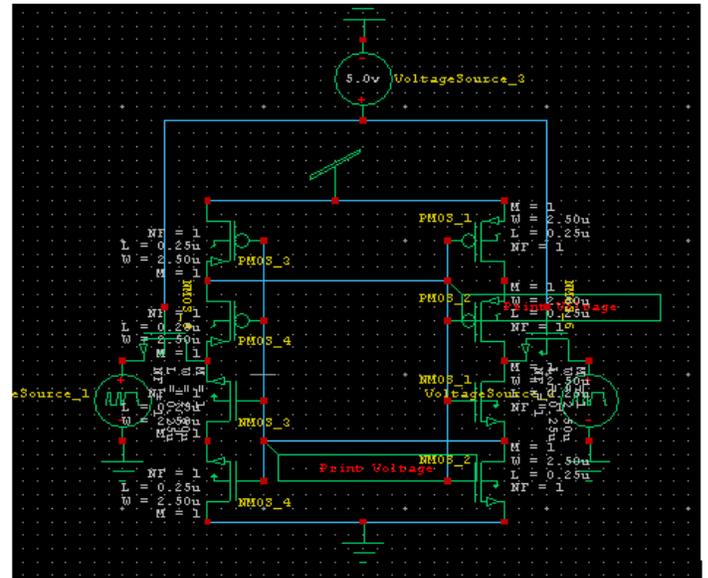
**TABLE-I**  
POWER DISSIPATION, DELAY AND POWER DELAY PRODUCT OF THE EXISTED 10T SRAM CELL

Power (Watts)	Delay (Seconds)	Power delay product ( $\times 10^{-15}$ wattsec)
4.78W	2.08	5.67

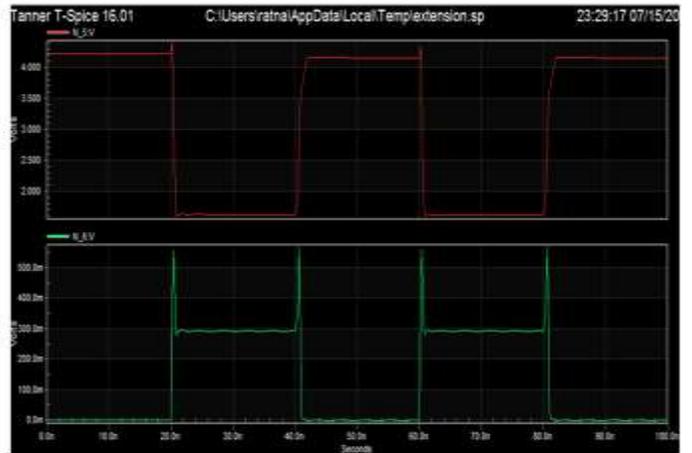
**TABLE-II**  
POWER DISSIPATION, DELAY AND POWER DELAY PRODUCT OF THE PROPOSED 10T SRAM CELL

Power (Watts)	Delay (Seconds)	Power delay product ( $\times 10^{-15}$ wattsec)
1.61	0.50	4.00

**SCHMATIC**



**WAVE FORMS**



**COMPRESSION OF DIFFERENT SRAMS PARAMETERS**

PARAMETERS EXISTING	6T	8T	10T
POWER DELAY PRODUCT ( $\times 10^{-15}$ WATTSEC)	6.25	6.21	5.67
POWER (mW)	6.76	4.72	4.78
DELAY (SECONDS)	1.98	2.01	2.08
PROPOSED POWER DELAY PRODUCT ( $\times 10^{-15}$ WATTSEC)	4.74	4.54	4.00
POWER (mW)	1.76	1.70	1.61
DELAY (SECONDS)	0.83	0.59	0.50

## **CONCLUSION**

A conclusions segment ought to be incorporated and it can be explicitly mentioned that that the voltage level is the most successful strategy for minimizing energy dissipation. SRAMs limit energy dissipation not only because of the restriction in voltage supply, but also because of the temperature and frequency of operation. Both of the above statistics indicate that, in terms of the frequency or temperature spectrum of all other design strategies for SRAM, 10 T cell SRAM with 18 nm tech is stronger. This article aims to find an effective SRAM data point with regard to energy usage and pace in various technology as long as the drug is power delayed.

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